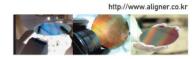
Spin coater

The Development and the commercialization of the Mask Aligner for wafer Midas System will continue to grow along with the value creation for our customers,





The MIDAS Spin coater system is good for research and variable process of all applications. It represents next generation of full-field Coating systems.



ITEM	SPECIFICATIONS
Substrate Size	2"~ 8" diameter
Max. rotation speed	100 ~ 6000rpm, AC motor
RPM Uniformity	0.1%
Dispenser(option)	1. Photoresist 2. EBR 3 Back-rinse
Dimension(mm)	650×950×1200(W×D×H) Weight: 250Kg



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